

Stepwise Structural Evolution of a DTS-F₂BT Oligomer and Influence of Structural Disorder on OFET and OPV Performance

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Supporting information

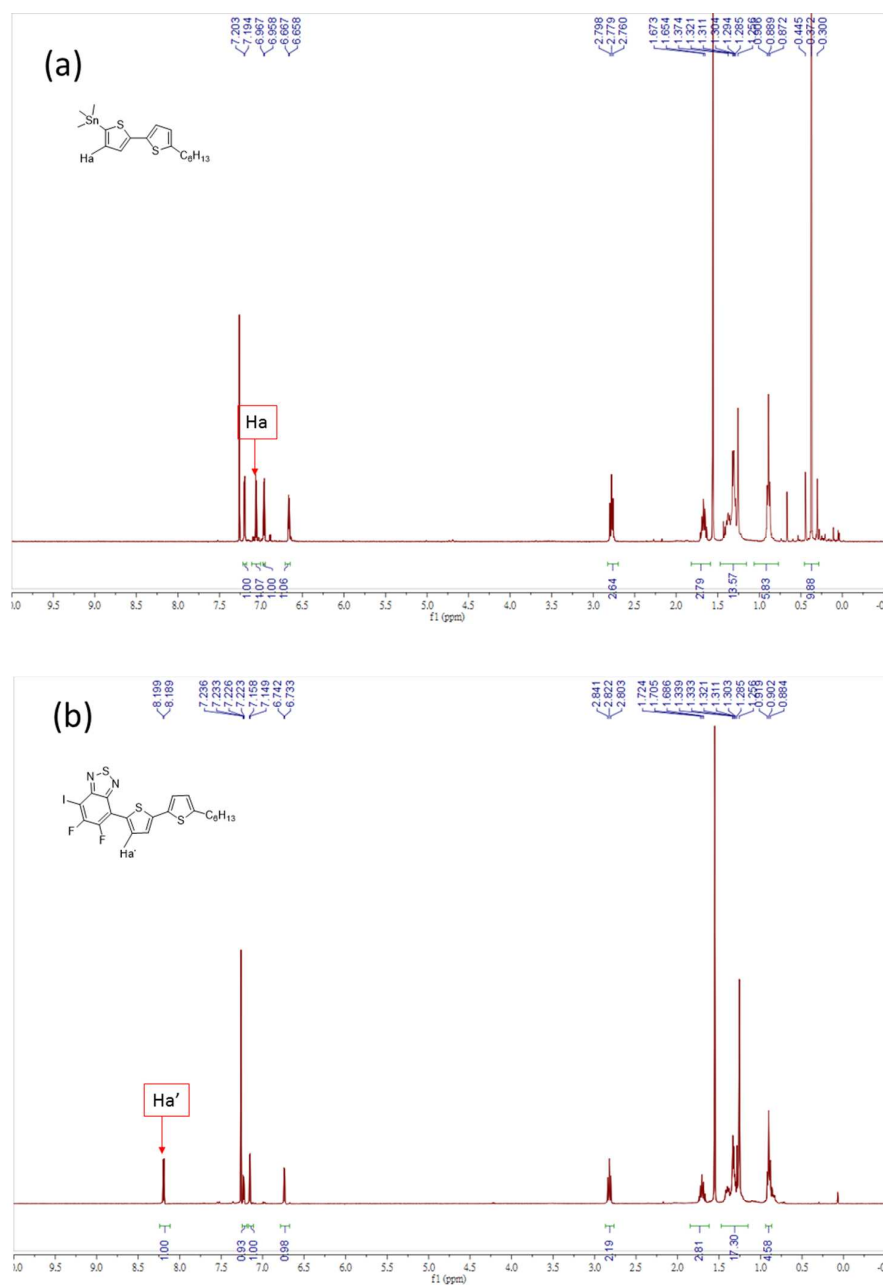


Figure S1. ^1H NMR spectra of (a) **2** and (b) **3**

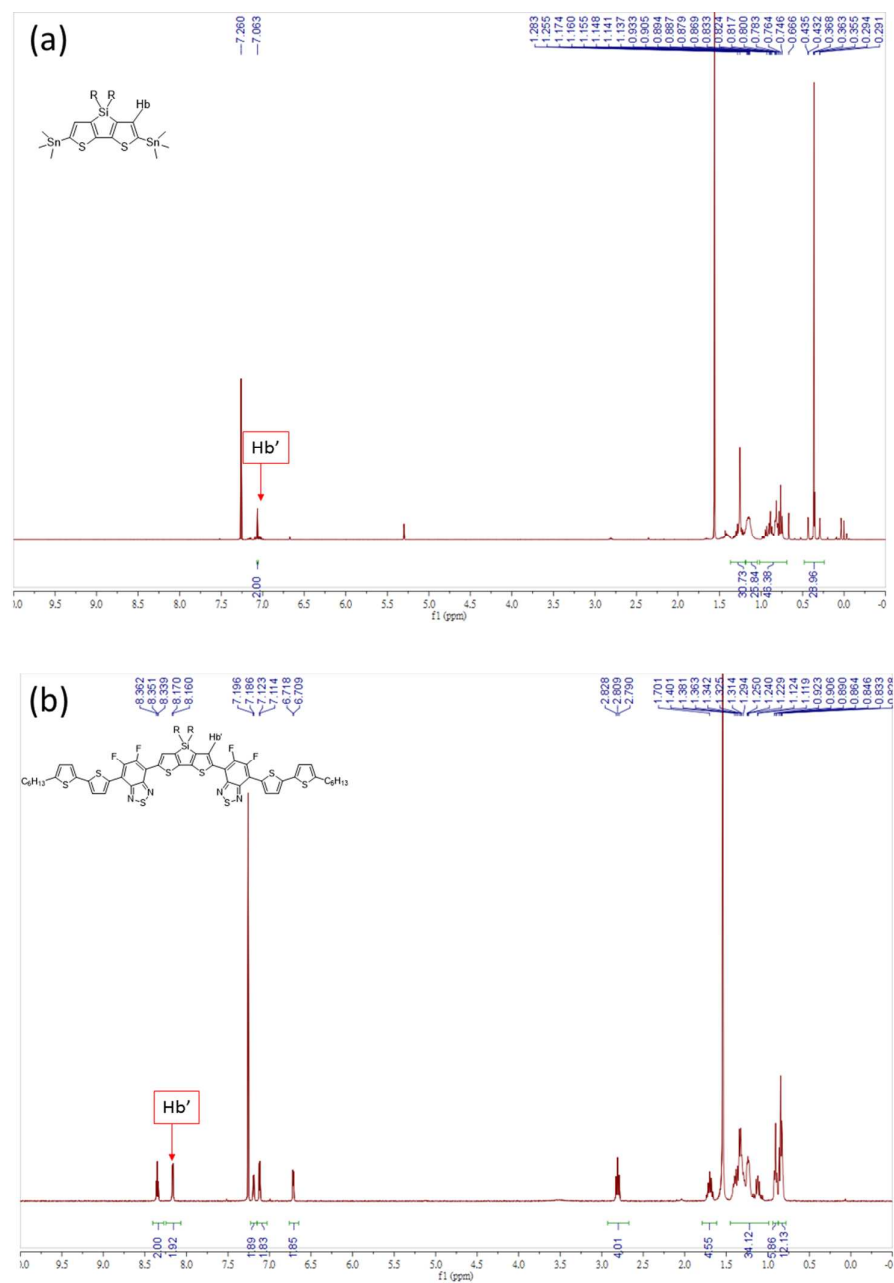
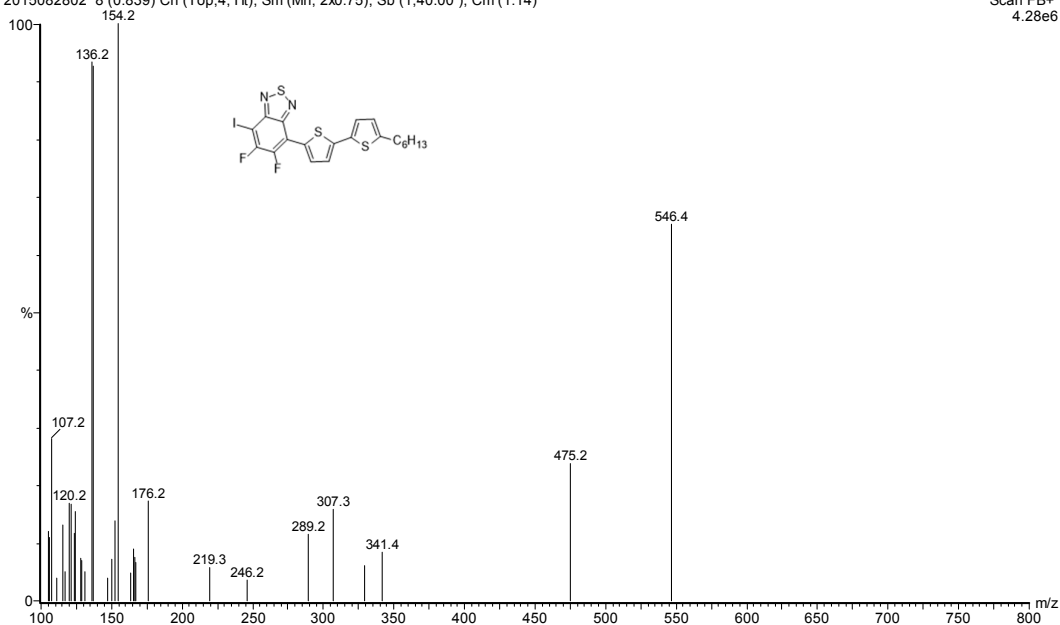


Figure S2. ^1H NMR spectra of (a) **4** and (b) **DTS(F₂BT)₂**

(FBT)Th2(3NBA)

2015082802 8 (0.839) Cn (Top,4, Ht); Sm (Mn, 2x0.75); Sb (1,40.00); Cm (1:14)

Scan FB+
4.28e6



DTS(FBTTh2)2(3NBA)

103031705 1 (0.127) Cn (Cen,4, 90.00, Ht); Sm (SG, 4x1.00); Sb (1,20.00); Cm (1:14)

Scan FB+
5.21e5

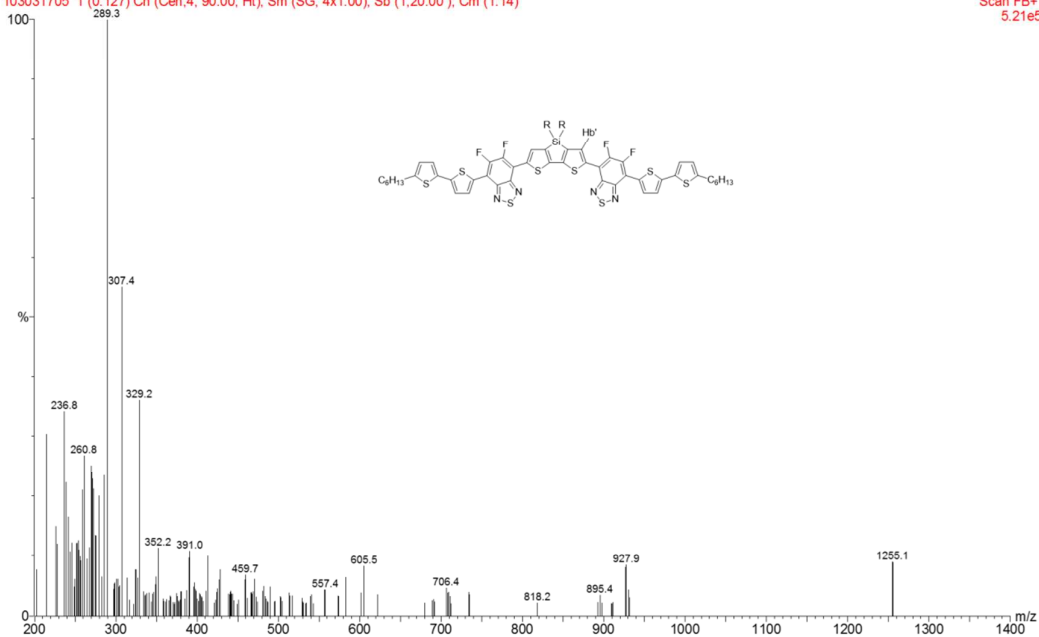


Figure S3. Mass spectra of (a) **3** and (b) DTS(F₂BT)₂.

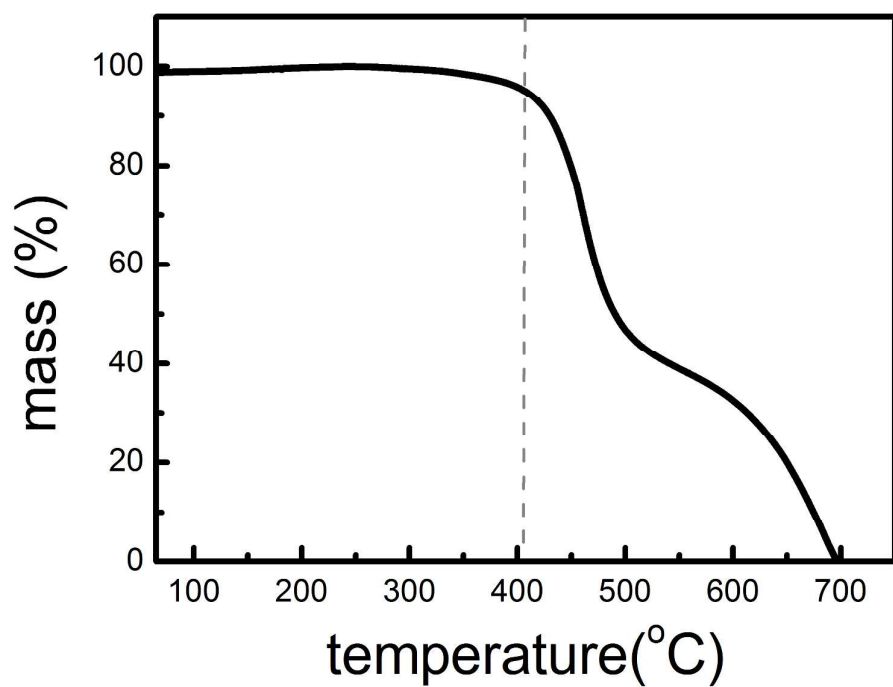


Figure S4. Thermogravimetric analysis of DTS(F₂BT)₂. The temperature of dissociation is 406 °C.

Table S1. Crystallographic Parameters of DTS(F₂BT)₂ from GI-XRD

(<i>hkl</i>)	<i>d</i> _{obs.} /nm	<i>d</i> _{calc.} /nm	<i>I</i> _{exp}	φ	(<i>hkl</i>)	<i>d</i> _{obs.} /nm	<i>d</i> _{calc.} /nm	<i>I</i> _{exp}	φ
(200)	2.27	2.27	100	π	(101)	2.31	2.29	1.96	π
(400)	1.15	1.13	24.88	π	(201)	1.28	1.72	2.96	0
(600)	0.77	0.76	4.97	π	(301)	1.23	1.31	1.51	π
(110)	0.93	0.93	1.34	0	(102)	1.05	1.27	1.31	0
(210)	0.88	0.88	1.36	0	(202)	1.15	1.14	1.22	π
(310)	0.82	0.80	2.06	0	(302)	0.98	1.00	1.23	0
(510)	0.67	0.67	1.57	0	(402)	0.83	0.86	1.27	π
(720)	0.4	0.38	1.47	0	(502)	0.73	0.75	1.27	0
(120)	0.46	0.47	0.95	0	(602)	0.60	0.66	1.29	π
(020)	0.48	0.48	1.21	π	(702)	0.51	0.58	2.07	0
-	-	-	-	-	(703)	0.47	0.52	1.21	π
<i>a</i> = 4.54 nm; <i>b</i> = 0.96 nm; <i>c</i> = 2.65 nm									
<i>α</i> = <i>β</i> = <i>γ</i> = 90°									

Table S2. Crystallographic Parameters of DTS(F₂BT)₂ from 2D WAXD

(<i>hkl</i>) plane	Experimental <i>d</i> -spacing <i>d</i> _{obs.} /nm	Theoretical <i>d</i> -spacing <i>d</i> _{calc.} /nm
(200)	2.3	2.27
(400)	1.15	1.14
(600)	0.76	0.76
(020)	0.49	0.48
(11 1 0)	0.43	0.38
(002)	1.36	1.33
(003)	0.91	0.88
(402)	0.82	0.86
(006)	0.47	0.44
(502)	0.64	0.75
(106)	0.44	0.44
(206)	0.42	0.43
(107)	0.39	0.38

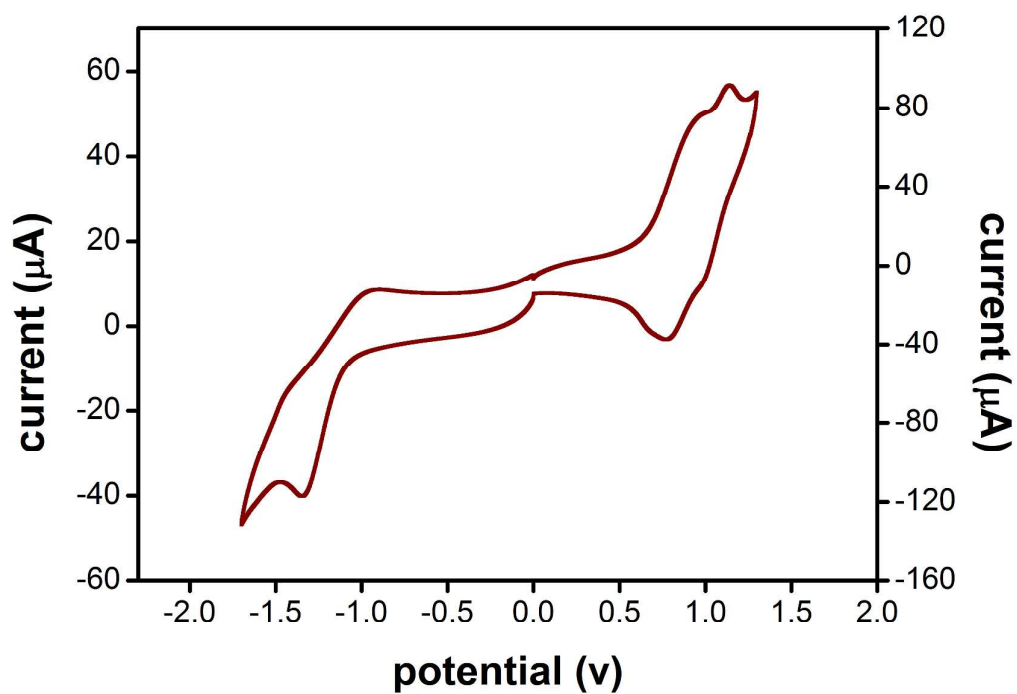


Figure S5. Cyclic voltammograms of DTS(F₂BT)₂ (10⁻³ M) in CH₂Cl₂ at scan rate 20 mV/s, with working and counter electrodes Pt and reference electrode Ag/AgCl; supporting electrolyte *n*-Bu₄NPF₆ (0.1 M).

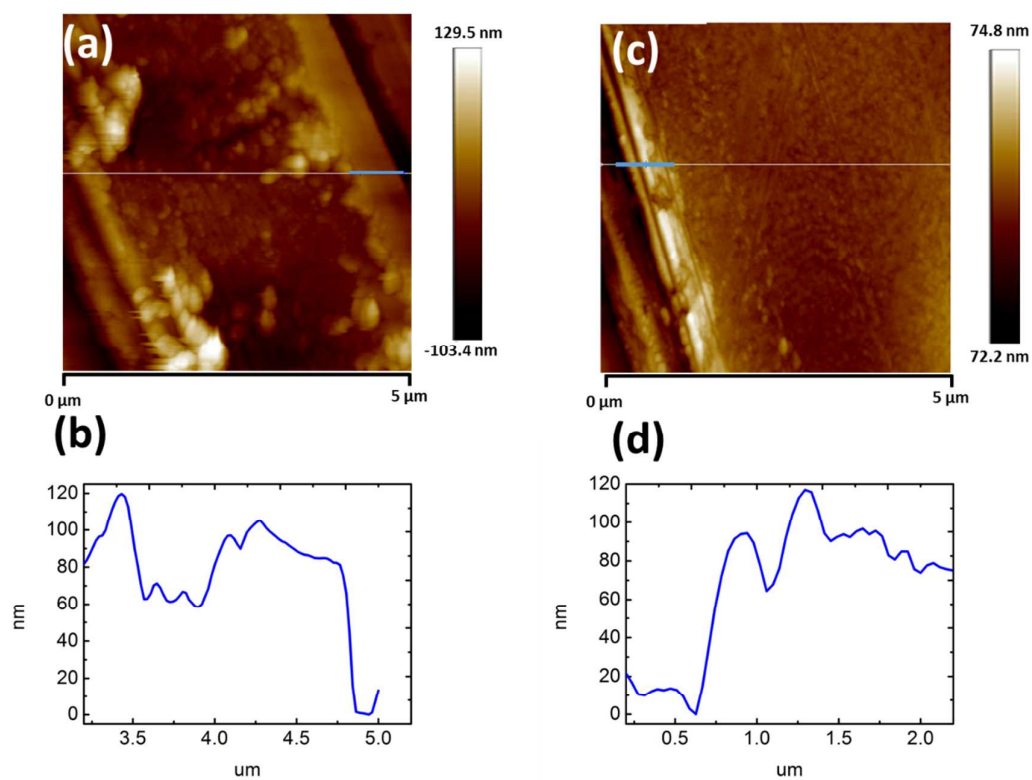


Figure S6. AFM topography and cross-section profiles of the DTS(F₂BT)₂:PC₇₁BM active films processed without DIO (a), (b) and with DIO (c),(d).

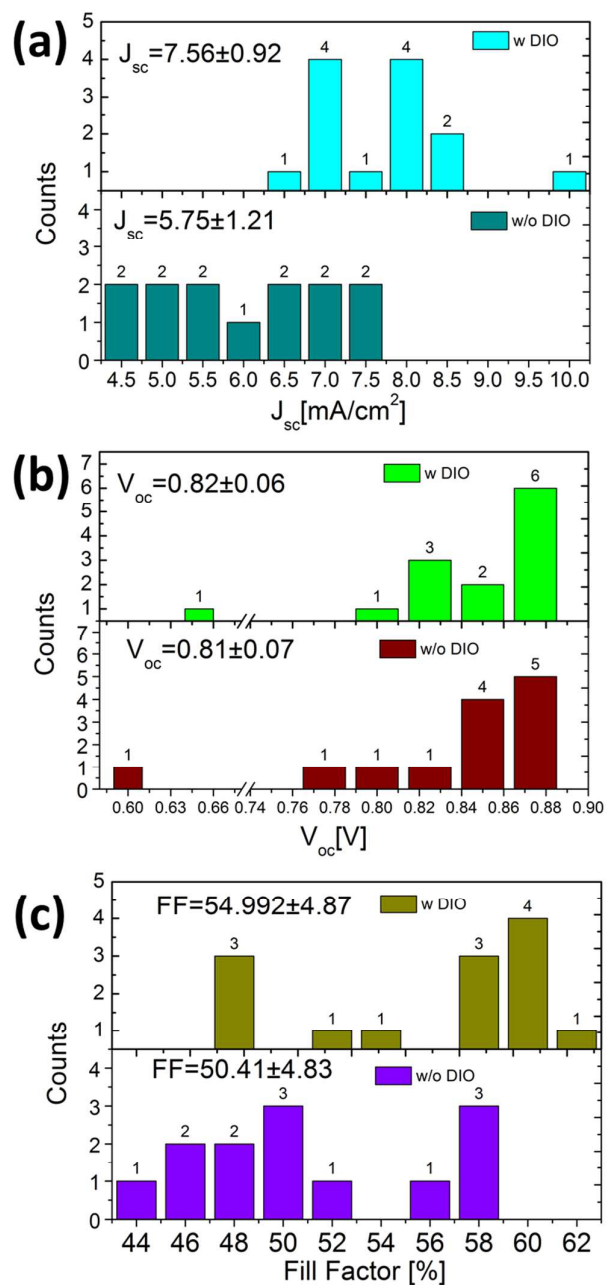


Figure S7. Histograms of (a) J_{sc} , (b) V_{oc} , and (c) Fill Factor for sets of DTS(F₂BT)₂–PC₇₁BM-based inverted BHJ PSC devices processed with and without DIO (0.4 vol %). Each sets is composed of 13 separate devices.